





Acceptor removal in silicon pad diodes with different resistivities

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Acceptor removal

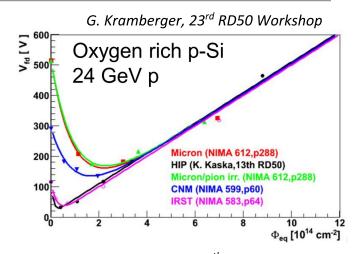
- •Apparent dopant removal due to the irradiation
- Parameterization as

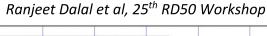
$$N_{eff}(\Phi) = N_{eff0}.e^{-c\cdot\Phi} + g_c\Phi$$

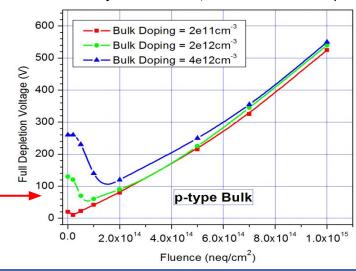
 For neutron irradiation, incomplete acceptor removal is also considered $(N_c < N_{eff0})$

$$N_{eff}(\Phi) = N_{eff0} - N_c \left(1 - e^{-c\Phi} \right) + g_c \Phi$$

Simulation can qualitatively reproduce this behaviour without Boron removal



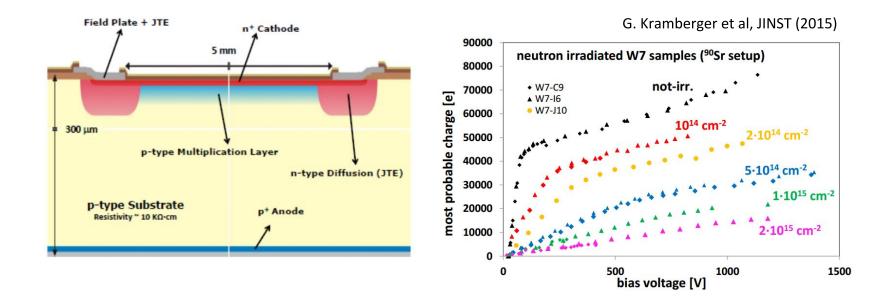




Motivation

Example: Low Gain Avalanche Detectors (LGADs)

- LGADs have a highly doped layer to achieve gain
- Interesting for their timing capabilities
- However, the gain decreases when exposed to radiation due to 'acceptor removal'



Motivation

Example #2: HVCMOS

 HVCMOS is an interesting technology for monolithic pixel sensors

 However, its charge collection varies with fluence

Increase of CCE with fluence due to 'acceptor

charge [e]

3500

2500

2000

1500

1000

500

0

■ ·2e14 cm-2

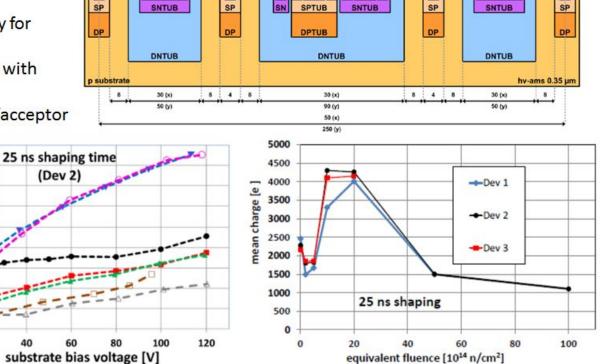
- 5e14 cm-2

-- 1e15 cm-2

2e15 cm-2 5e15 cm-2

-A-1e16 cm-2

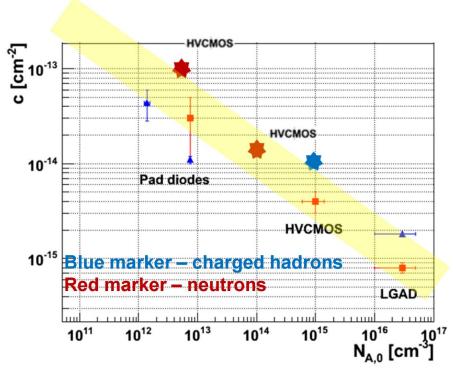
removal' observed



A. Affolder et al, J. Instrumentation (2016)

Motivation

No systematic study, hard to compare results from literature:



- Different devices
- Different oxygen content
- Different material types
- Different measurement techniques

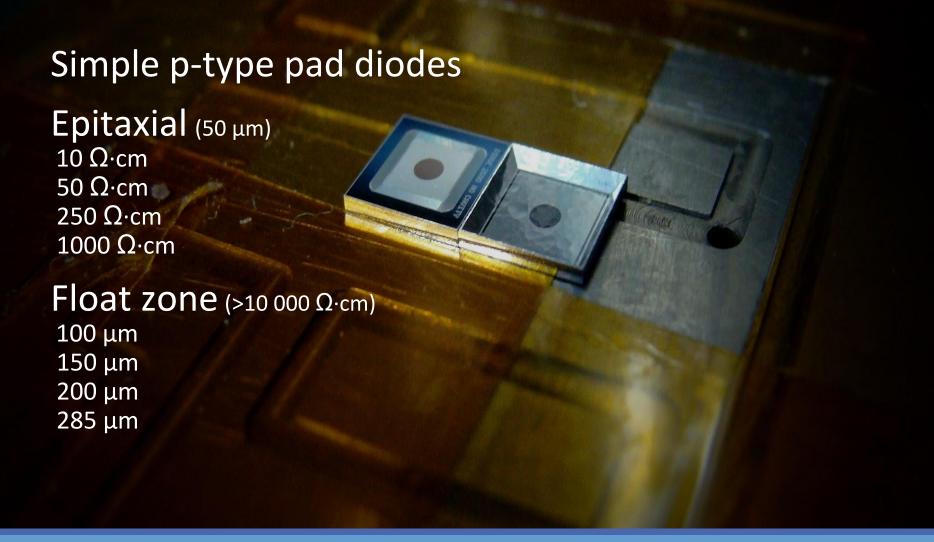
G. Kramberger, VERTEX (2016)

Solution: dedicated characterization experiment

A large number of sensors with the same structure with varying thicknesses, resistivities and material types

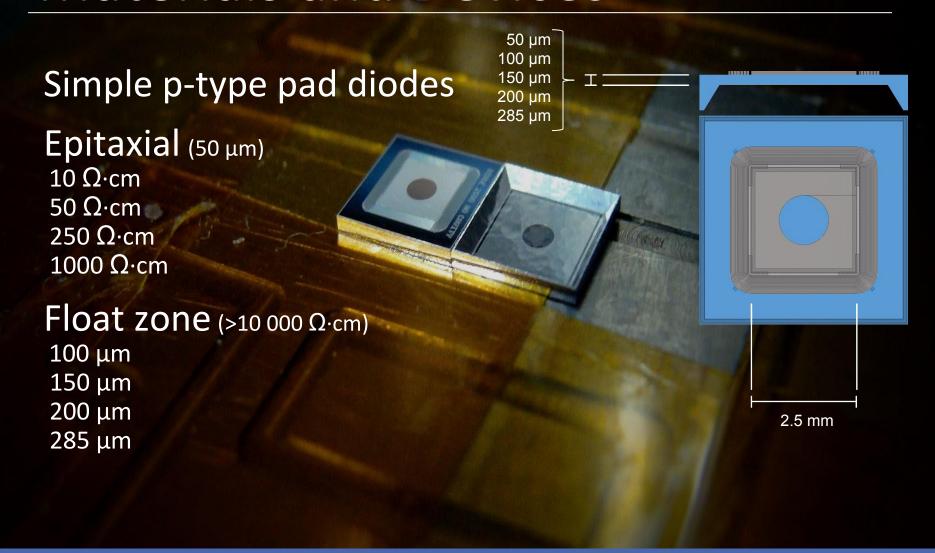


Materials and Devices





Materials and Devices



Irradiation





From ~ $7x10^{13}$ to $7x10^{15}$ n_{eq} cm⁻²







Acceptor Removal Used Methods

From CV curves, two methods were used to measure Neff:

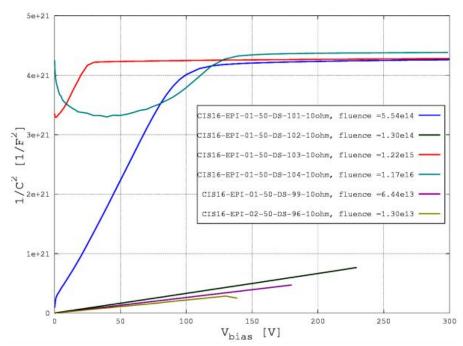
• Depletion Voltage*:

$$N_{eff} = \left(\frac{C}{A}\right)^2 \frac{2V_{dep}}{\varepsilon \varepsilon_0 q_0}$$

•1/C² Slope:

$$N_{eff} = \frac{2}{A^2 \varepsilon \varepsilon_0 q_0} \frac{1}{d \left(1/C^2 \right) / dV}$$

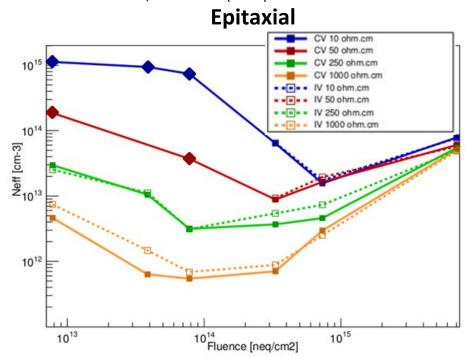
Epitaxial (10 Ωcm; @-20°C; annealing: 10min 60°C)



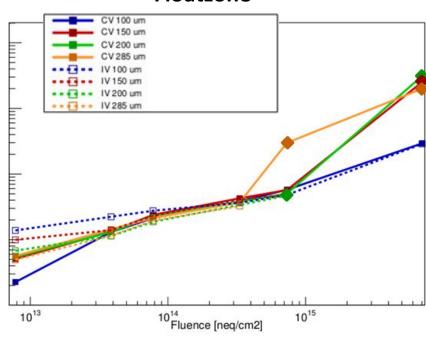
^{*}This method was also applied to IV curves

Acceptor Removal Previous Results

P. Almeida et al, 30th RD50 (2017)

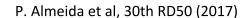






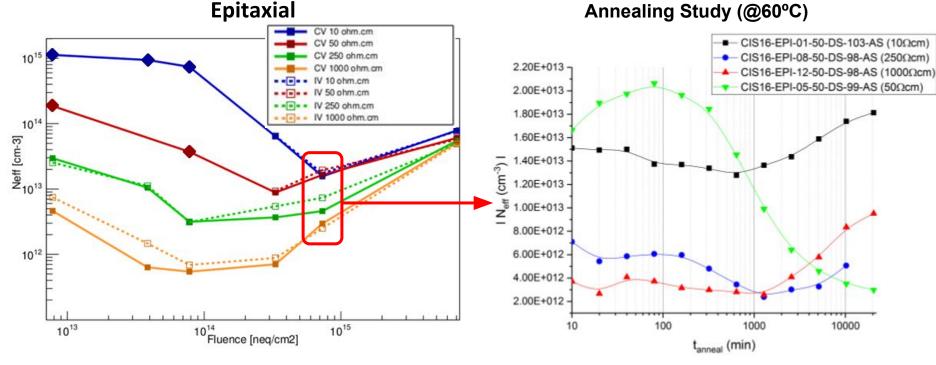
- from CV/IV kink: $N_{eff} = \left(\frac{C}{A}\right)^2 \frac{2V_{dep}}{arepsilon arepsilon_0 q_0}$

Acceptor Removal Annealing Study



P. Almeida et al, 31st RD50 (2017)





from CV/IV kink:

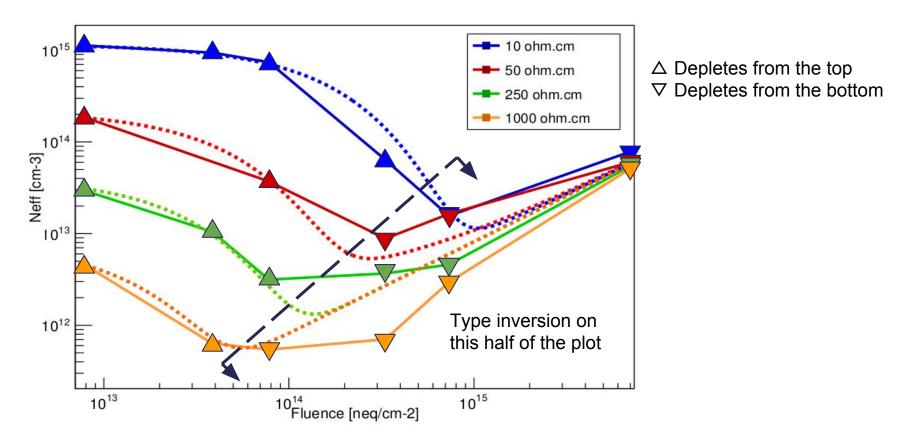
$$N_{eff} = \left(\frac{C}{A}\right)^2 \frac{2V_{dep}}{\varepsilon \varepsilon_0 q_0}$$

from CV slope:

$$N_{eff} = \frac{2}{A^2 \varepsilon \varepsilon_0 q_0} \frac{1}{d \left(1/C^2 \right) / dV}$$

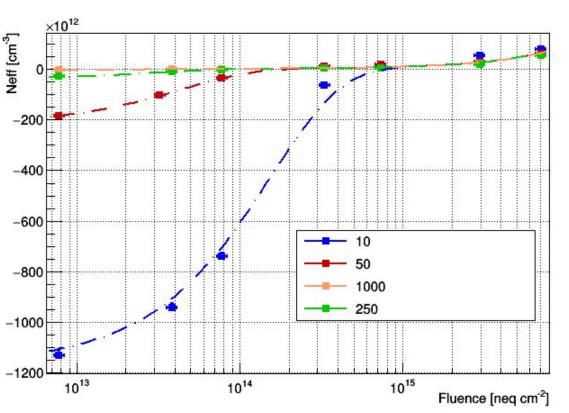
Annealing curves show evidence of type inverted detectors — later confirmed by TCT. For more details, see dedicated presentation in the 31st RD50 workshop.

Acceptor Removal Type Inversion



Every detector was measured in TCT (top, bottom and infrared) and checked for type inversion — at higher fluences half of the plot was found to be **type inverted**.

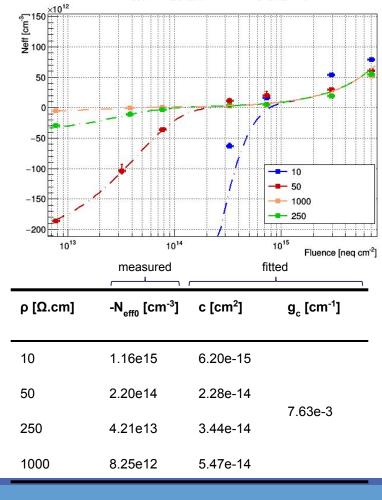
Acceptor Removal by Proton Irradiation



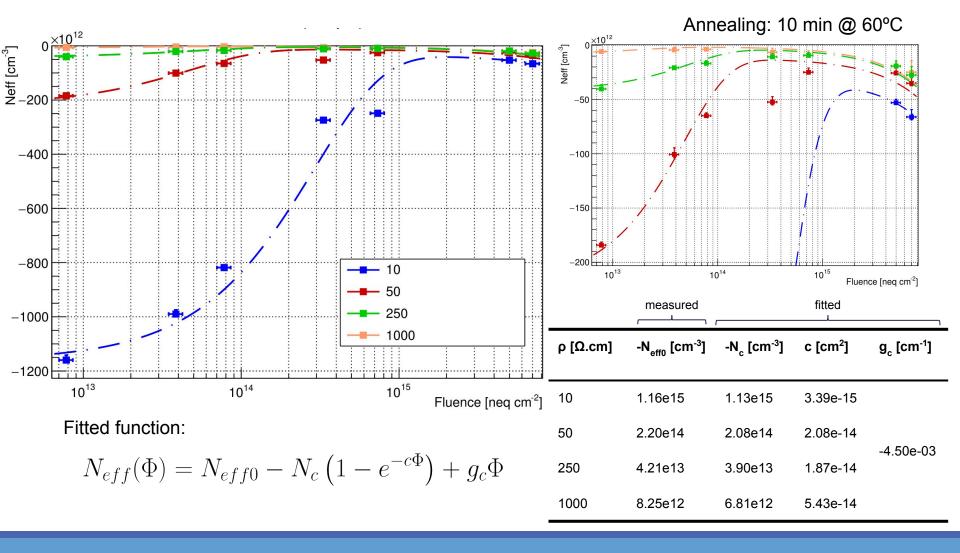
Fitted function:

$$N_{eff}(\Phi) = N_{eff0}.e^{-c\cdot\Phi} + g_c\Phi$$

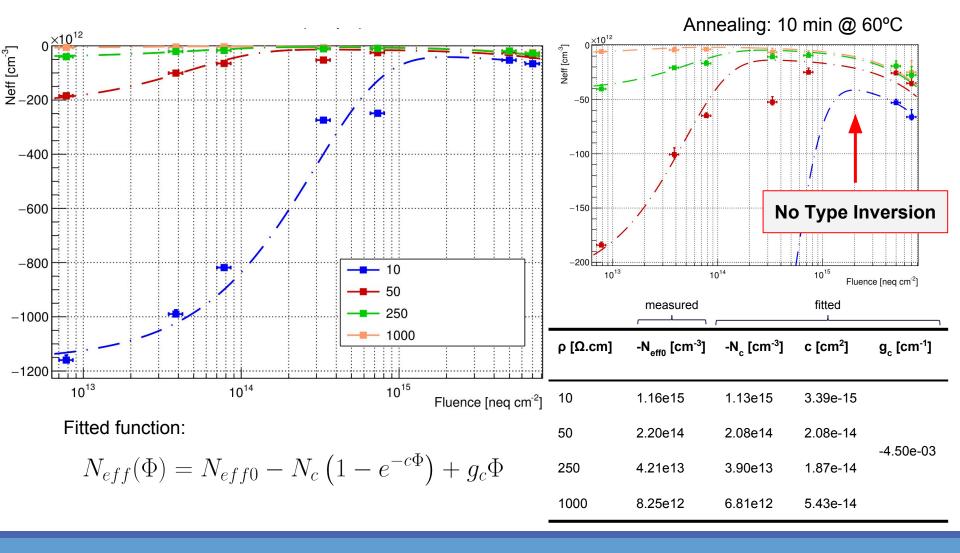
Annealing: 10 min @ 60°C



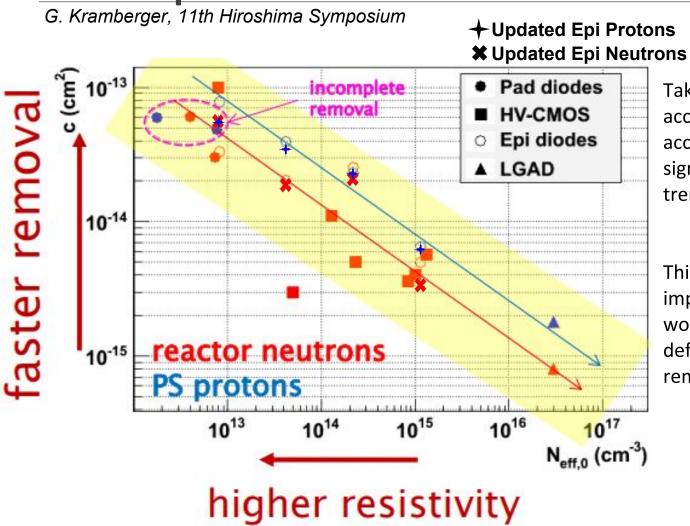
Acceptor Removal by Neutron Irradiation



Acceptor Removal by Neutron Irradiation



Acceptor Removal



Taking type inversion into account doesn't change the acceptor removal rate **c** in a significant way, keeping the trend previously seen.

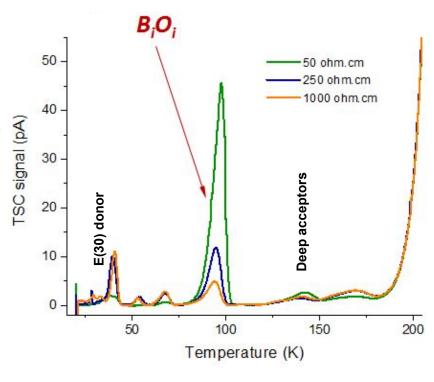
This parametrization is important by itself, but we would like to understand the defect dynamics of acceptor removal

Thermally Stimulated Current (TSC)

- Gives a spectrum of the defects in the detector by measuring the leakage current while ramping up the temperature
- Allows for the estimation of defect concentration by measuring released charge by the defect's peak

There is a clear dependence of the B_iO_i peak with the initial Boron concentration. Suggesting that the main mechanism for acceptor removal is:

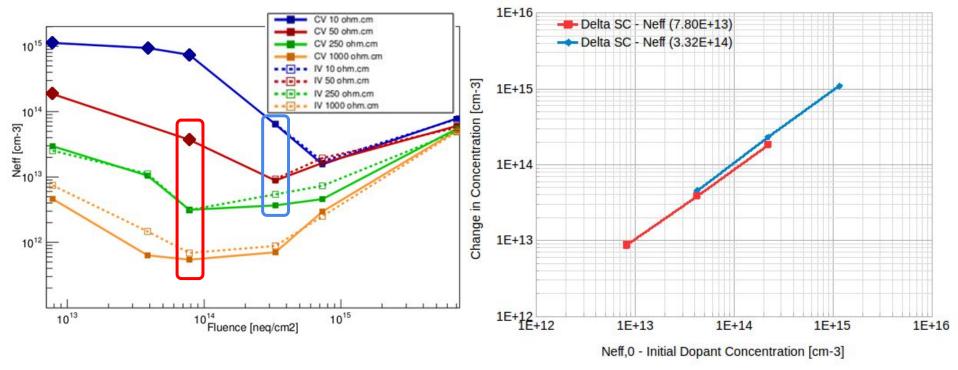
$$\begin{cases} I + B_s \to B_i \\ B_i + O_i \to B_i O_i \end{cases}$$



 $50 \mu m$, $Φ_{neq} = 7.80 \cdot 10^{13} \text{ cm}^{-2}$, 10 min @ 60°C annealing

Macro vs Micro

Is there a match between defects observed through TSC and the measured $N_{\rm eff}$ from CV?

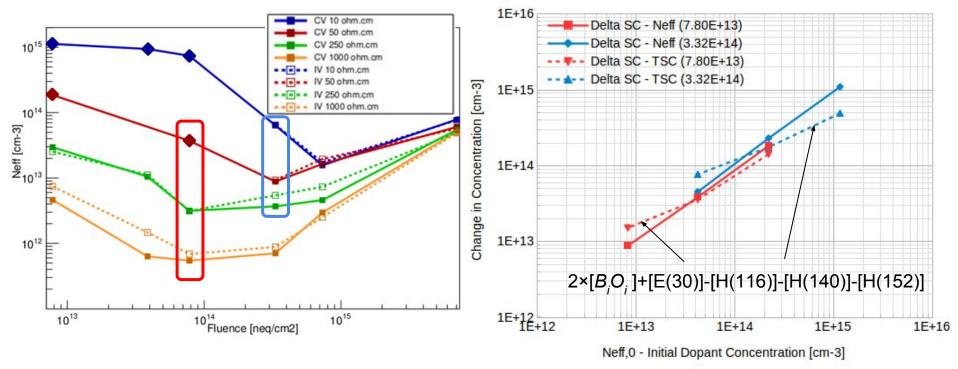


Assumptions:

- E(30) are donor like defects and contribute positive space charge
- H(116)-H(140)-H(152) are acceptor like defects and contribute negative space charge
- B_iO_i contributes twice its concentration

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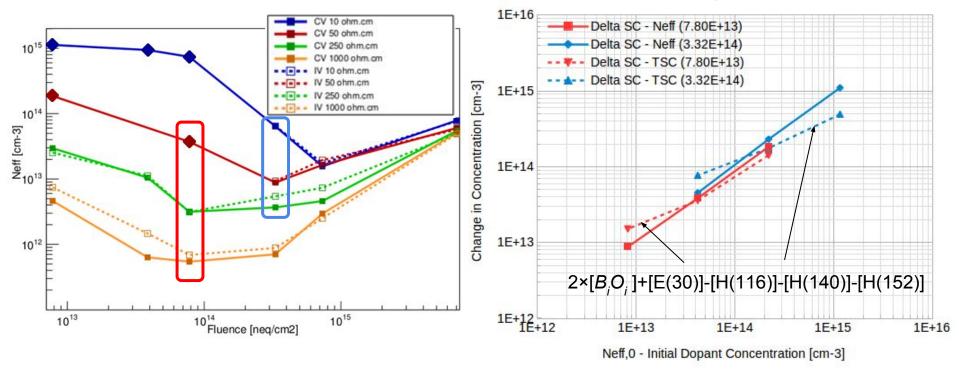


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Macro vs Micro

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There is a clear correlation between the concentration of the defects observed through TSC, and the Neff change measured by CV

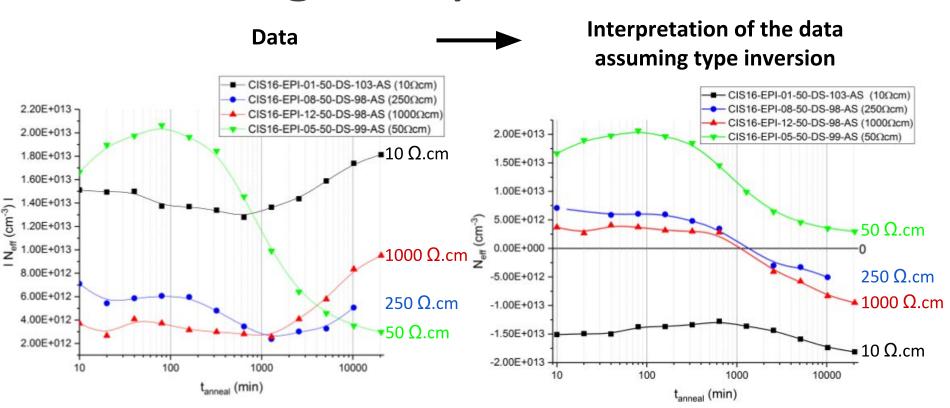
Summary and Outlook

Work in progress to study acceptor removal:

- CV, IV, TCT and TSC was used to investigate the evolution of Neff vs fluence of detectors of different resistivities irradiated by protons and neutrons
- An annealing study and TCT measurements confirmed type inversion in some of the proton irradiated detectors
- After correction for type inversion, Neff vs fluence plots were fitted to extract the acceptor removal parameter c
- Strong dependence between B_iO_i production and resistivity was detected by TSC measurements
- We want to perform SIMS measurements, as we don't know the Oxygen concentration at the moment
- We're improving our TSC setup to study the B_iO_i defect in more detail

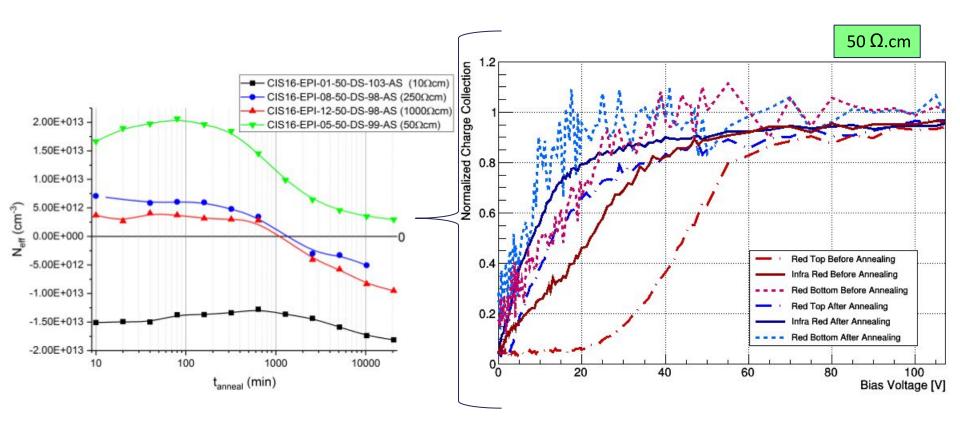
Spare Slides

Annealing Study Interpretation of Neff



- Annealing at 60°C
- Up to 20480 min or ~14 days of accumulated annealing
- Neff calculated from CV measurements

Annealing Study TCT confirmation



Acceptor Removal

